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PATENT
Attorney Docket No. 553-001.002PCT
#3IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Michael Gangyu KONG et al. : Intl. Application No.: **PCT/IB03/003485**Serial No.: **10/523,963**: Intl. Filing Date: **August 7, 2003**Filed: **February 7, 2005**: Priority Date: **August 7, 2002**For: ***Generation of Diffuse Non-Thermal Atmospheric Plasmas***Director of the U.S. Patent and Trademark Office
P.O. Box 1450
Alexandria, VA 22313-1450**INFORMATION DISCLOSURE STATEMENT**

Sir:

Applicants submit herewith references of which they are aware, which they believe may be material to the examination of this application and in respect of which they may have a duty to disclose in accordance with 37 CFR §1.56.

While this Information Disclosure Statement (IDS) may be "material" pursuant to 37 CFR §1.56(b), it is not intended to constitute an admission that any document referred to herein is "prior art" for this invention unless specifically designated as such.

I hereby certify that this correspondence and all documents referred to as being enclosed are being deposited with the United States Postal Service on this date, **June 22, 2005**, in an envelope with sufficient postage as, "First Class Mail," addressed to the Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450.



Lissette Ramos

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /M.S./

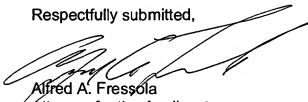
In accordance with 37 CFR §1.97(g), the filing of this IDS shall not be construed to mean that a search has been made or that no other material information as defined under 37 CFR §1.56(a) exists.

Enclosed is an International Search Report dated October 29, 2003 issued in International Patent Application No. PCT/IB03/03485 (filed on August 7, 2003), from which the present application now requests entry into the US national phase.

Also enclosed is a Form PTO-1449 listing the cited references. Copies of the cited non-US references are also enclosed herewith. Copies of the cited US references are not enclosed pursuant to the USPTO waiver of the requirement to submit copies of US references. The relevance of each reference is specifically explained in either the Search Report or the application specification, or is otherwise considered to be relevant, and the abstract of each reference provides a concise explanation thereof.

This IDS is being submitted before receipt of a first Official Action in this matter; therefore, the undersigned respectfully submits that no fee is due for filing this IDS. The Commissioner is hereby authorized to charge to deposit account 23-0442 any fee deficiency required to submit this IDS.

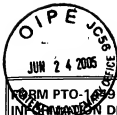
Respectfully submitted,



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Dated: June 22, 2005

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FORM PTO-1059
INFORMATION DISCLOSURE STATEMENT

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553-001.002

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10/523,963

APPLICANT: Michael Gangyu KONG et al.

FILING DATE:

February 7, 2005

ART UNIT:

To Be Assigned

UNITED STATES PATENT DOCUMENTS

EXAM. INITIAL	DOCUMENT NUMBER	DATE	INVENTOR/ASSIGNEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	4,370,526	Jan. 25, 1983	<i>Schoofs et al.</i>			
	6,106,659	Aug. 22, 2000	<i>Spence et al.</i>			
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FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO
WO 9713266	Apr. 10, 1997	PCT			
JP 62077479	Sep. 4, 1987	Japan			

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

	"Freedom to Use" Search of GB 0218299.6; "Generation of Diffuse Non-Thermal Atmospheric Plasmas;" Dr. Michael Kong
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Examiner: (To be assigned) Melissa Stalder/

Date: 07/16/2008

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	"Air Pollution Control by Electrical Discharges;" R. Hackam et al; IEEE Transactions on Dielectrics and Electrical Insulation, Vol. 7, No. 5, October 2000.
	"Generation of Large-Volume, Atmospheric-Pressure, Nonequilibrium Plasmas;" E.E. Kunhardt; IEEE Transactions on Plasma Science, Vol. 28, No. 1, February 2000.
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	"A Survey of Electron Swarm Data;" J. Dutton; J. Phys. Chem. Ref. Data, Vol. 4, No. 3, 1975.
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